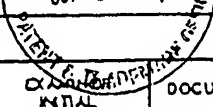


Form PTO-1449

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

OCT 29 2003



(Use several sheets if necessary)

Docket Number (Specimen)

TSMC-01-1388

Application Number

10/628,914

Applicant

Chih-Ming Ke et al.

Filing Date

07/29/03

Priority Art Unit

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>AK</i>	611468	19/5/00	Komatsu	250	201.3	6/4/98
<i>lee</i>	591671	6/29/99	Butsch et al.	430	30	3/13/97
<i>lee</i>	6130432	10/10/00	Pfeiffer et al.	250	396ML	4/13/99
<i>lee</i>	5025165	6/18/91	Chen et al.	250	491.1	3/26/90
<i>lee</i>	6066849	5/23/00	Masnaghetti et al.	250	310	9/8/98

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
					YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Portmanteau Pages, Etc.)

<i>lee</i>	"193nm resist shrinkage", by Su et al., Solid State Technology, May 2001, pp. 52-54 and 57.
<i>lee</i>	U.S. Patent Application Serial No. 10/047,266, Filed 1/14/02,
<i>lee</i>	"Reducing Photoresist Shrinkage via Plasma Treatment",
	assigned to the same assignee.

EXAMINER

ZIA R. HASHMI

DATE CONSIDERED

12/28/04

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.